

High Density Low Cost Stacked 3D NAND with Hybrid Bonding

Memory array and logic disaggregation 64, 96, 128 layers and beyond for 3D NAND



Data Centers



AI, Machine Learning & Deep Learning Hardware



Automotive



Gaming

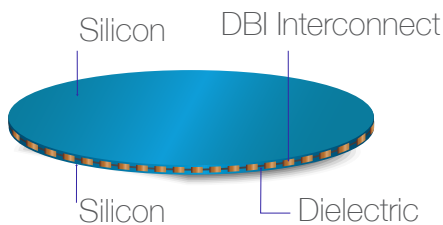
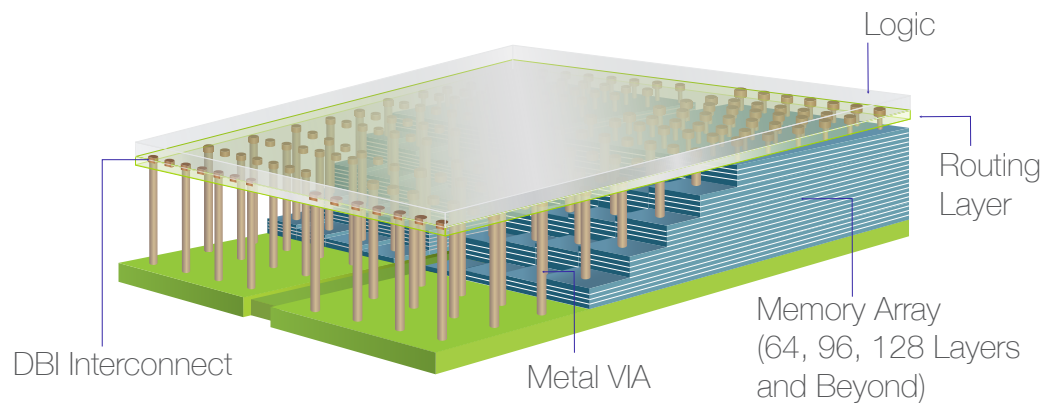


Consumer Electronics



Industrial & Scientific

DBI® Enabling Next-Gen Stacked 3D NAND



DBI Hybrid Bonding with Metal Interconnect

DBI Hybrid Bonding Benefits

With DBI technology, 3D NAND and Logic wafers can be bonded with exceptionally fine pitch 3D interconnect.

- Low temperature bonding
- Memory array and logic disaggregation
 - Technology node optimization
 - Yield enhancement
 - Die size reduction
 - High speed interfaces
- Fine pitch 3D interconnect scalable down to 1µm
 - Enables high bandwidth
- Reduces product development cycle

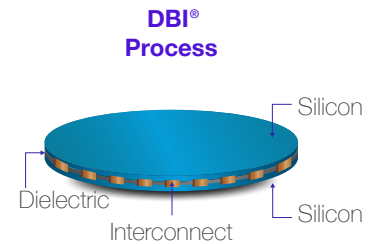
DBI® Technology

Direct Bond Interconnect (DBI) technology is a low temperature direct hybrid bonding solution that allows wafers or die to be bonded with exceptionally fine pitch 3D electrical interconnect. DBI can also minimize the need for Thru Silicon Vias (TSVs).

DBI technology is in high volume production today.

Features

3D Interconnect Metals	Cu, Ni			
3D Interconnect Pitch	Scalable to <math><1\mu\text{m}</math> pitch 1.6 μm demonstrated 6 μm in high volume production			
Bond Interface Materials	Integrated metal interconnect with: <table border="1" style="display: inline-table; vertical-align: middle;"> <tr> <td>SiO (TEOS, Thermal, Silane)</td> <td>SiN (CVD or PECVD)</td> <td>SiON (PECVD)</td> </tr> </table>	SiO (TEOS, Thermal, Silane)	SiN (CVD or PECVD)	SiON (PECVD)
SiO (TEOS, Thermal, Silane)	SiN (CVD or PECVD)	SiON (PECVD)		
Substrates	Same as ZiBond			
Bonding Temperature	Room Temperature			
Anneal Temperature	150-300°C (application dependent)			
Equipment	Industry standard wafer alignment and bonding equipment			



Hybrid Bonding with Metal Interconnect

